



**PUSAT PENGURUSAN MAKMAL  
UNIVERSITI (PPMU)**

Form Num.	UURL/F/133
Version	1/2023
Effective Date	01/02/2023
Equipment	PECVD
Sample Serial No.	

**MICRO/NANO FABRICATION & MACHINING LABORATORY  
SAMPLE SUBMISSION FORM (INDUSTRY)**

**General Rules and Requirements:**

- All information provided should be true
- Booking will be notified/updated by email
- Booking procedure
  - Submit the completed application form to UURL Sample Acceptance Counter
  - Fast Lane is offered to non-UTM customers with an additional 50% charge from the normal price**
- Sample Condition & Preparation
  - PPMU has the right to cancel any analysis if the sample is suspected to have a high risk to the safety of the operator or can cause damage to the instrument during the analysis. The cost of damages will be borne by the customer.**
  - The remaining samples will be disposed of within a month after the analysis is completed.**
- All enquiries regarding PECVD should be forwarded to the Science Officer (Mrs Nurnazmin Mohd Nordin, email: [nurnazmin@utm.my](mailto:nurnazmin@utm.my) or Assistant Engineer, Mr Muhammad Sulaiman Muhammad Zain, email: [m.sulaiman@utm.my](mailto:m.sulaiman@utm.my), tel: 07-5557729) or visit our website at [ppmu.utm.my](http://ppmu.utm.my).

1. APPLICANT'S PERSONAL PARTICULARS											
Name of Applicant											
Hand Phone No.											
Email											
Department/Division											
Signature & Official Stamp		*A digital signature is not recommended. Any matters raised in the future are beyond our responsibilities									
2. COMPANY DETAILS											
Name											
Registration No.											
Address											
Telephone No.											
Email											
Mode of Payment		<input type="checkbox"/>	Cash	<input type="checkbox"/>	EFT	<input type="checkbox"/>	Invoice	<input type="checkbox"/>	Fast Lane		
3. SAMPLE INFORMATION											
Total No. of Sample / Material											
Recipe Input		Substrate Temp. (°C)		Working Pressure (mTorr)		Process Time (sec)					
		Stable Time (°C)		RF Power (W)		Purge Time (sec)					
		Gases (sccm)									
		HiQ N <sub>2</sub>		Ar		N <sub>2</sub> O		NH <sub>3</sub>			
		GN <sub>2</sub>		SF <sub>6</sub>		SiH <sub>4</sub>		O <sub>2</sub>			
		He									
Solvent (ml)		SU-8 2002	SU-8 Developer	KMPR 1035	AZ IPS-6090 PR						
		SU-8 2010	Remover PG	AZ 1505 PR	AZ nLOF 2070 Negative Resist						
		SU-8 2075	AZ 40 XT – 11 D	Isopropanol	Acetone						
		AZ 826 MIF Developer	Technistrip P1316	Ethanol							
Remarks											